PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

VADIM YEVGENYEVICH BANINE et al.

Application No.:

10/748,851

Confirmation No.:

2813 2851

Filed:

December 31, 2003

Group No.:

Examiner:

For:

LITHOGRAPHIC APPARATUS HAVING A DEBRIS-MITIGATION SYSTEM.

A SOURCE FOR PRODUCING EUV RADIATION HAVING A DEBRIS MITIGATION

SYSTEM AND A METHOD FOR MITIGATING DEBRIS

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

SUPPLEMENTAL APPLICATION DATA SHEET 37 C.F.R. § 1.76(c)

The following information on the Application Data Sheet is changed as indicated:

BIBLIOGRAPHIC DATA

1. Applicant information is being modified.

SIXTH applicant ABRAHAM VEEFKIND

Citizenship

Dutch

Residence

Willem Alexanderpark 17, NL-2202 XW Noordwijk, The Netherlands

2. Assignee information is being added.

The assignee of this application is:

ASML NETHERLANDS B.V.

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Extent of interest of assignee in application: ENTIRE RIGHT, TITLE AND INTEREST

Date: July 1, 2004

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